

AGILENT WORKFLOW SERVICES: CAPILLARY FLOW TECHNOLOGY (CFT) BACKFLUSH TRAINING

The Measure of Confidence

Get training to improve GC and GC/MS data integrity, column life and sample throughput—fast!

Achieve results quickly with CFT Backflush Training

With Agilent CFT Backflush training, you'll be equipped to configure methods to shorten analysis time, backflush accumulated sample matrix, and prevent carryover that may compromise GC and GC/MS column performance. An Agilent service representative will provide training at your site and use one of your methods as an example to demonstrate how you can configure CFT Backflush for your hardware, software, and applications.

You'll get hands-on training on CFT Backflush setup and optimization

- Run the setup utility for CFT Backflush
- Determine the right CFT configuration for your selected application
- Establish proper set points for the configuration
- Migrate Retention Time Locking Curves to your new configuration
- Automate CFT timing, set point determination and method updates

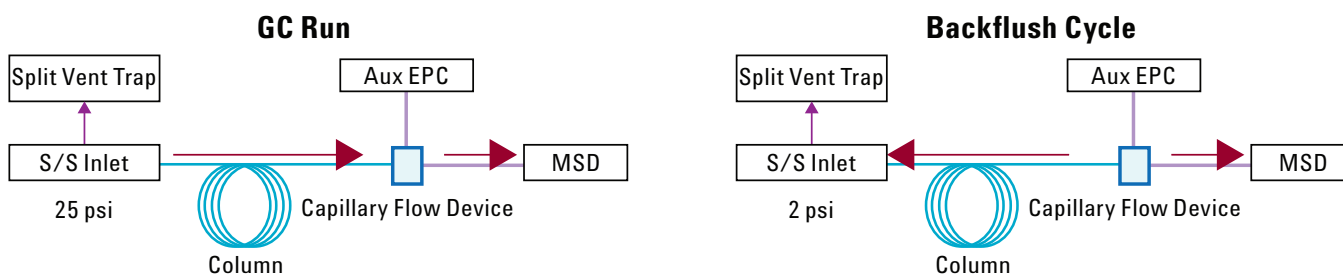
The sooner you implement CFT Backflush, the sooner you achieve the benefits.

For more information on Agilent Workflow Services: CFT Backflush, visit www.agilent.com/chem/backflush.

Enjoy the benefits of CFT Backflush now:

- Increase throughput and productivity with faster cycle times
- Boost uptime with less frequent column trimming and detector maintenance
- Improve sensitivity and data quality by reducing column bleed
- Cut costs by lengthening column life

*Agilent Workflow Services:
The fastest path to expert results*



Reversing column flow immediately after the last compound of interest has eluted using Capillary Flow Backflush technology can improve the quality of your analysis and save you time and money. The technique eliminates long bake-out times and high temperatures used to elute highly retained sample components. Instead, these materials are swept backwards through the column and out the split vent—preventing carryover, column fouling, retention time shifts, and MSD source contamination.

Information, descriptions and specifications in this publication are subject to change without notice.

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